

SUPPLEMENTARY DATA

Fabrication of Plasmonic Dye Sensitized Solar Cells using Ion Implanted Photoanodes

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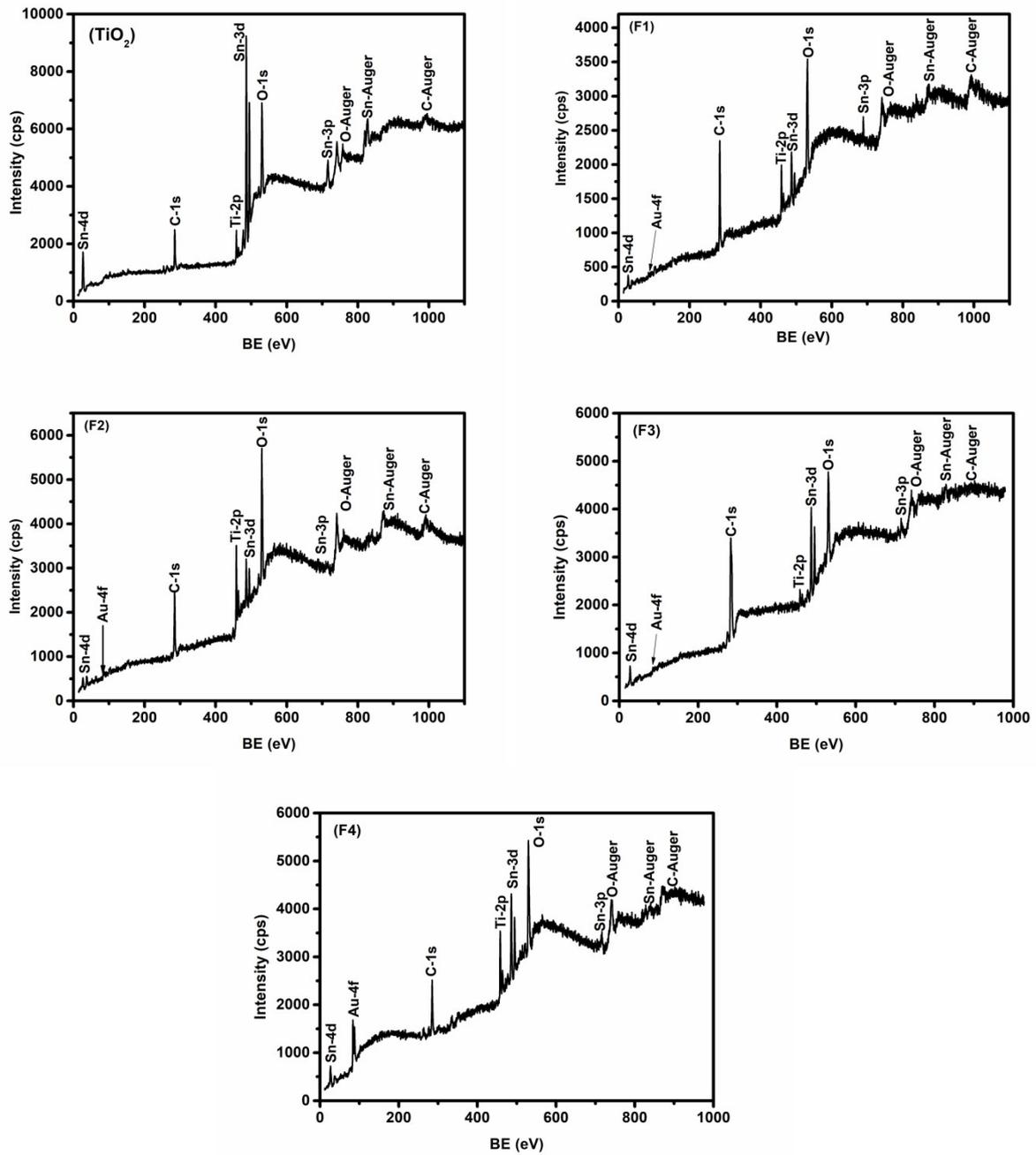


Fig. S1: XPS survey spectra of unimplanted TiO₂ and Au implanted TiO₂ matrix at different fluence (F1, F2, F3 and F4)

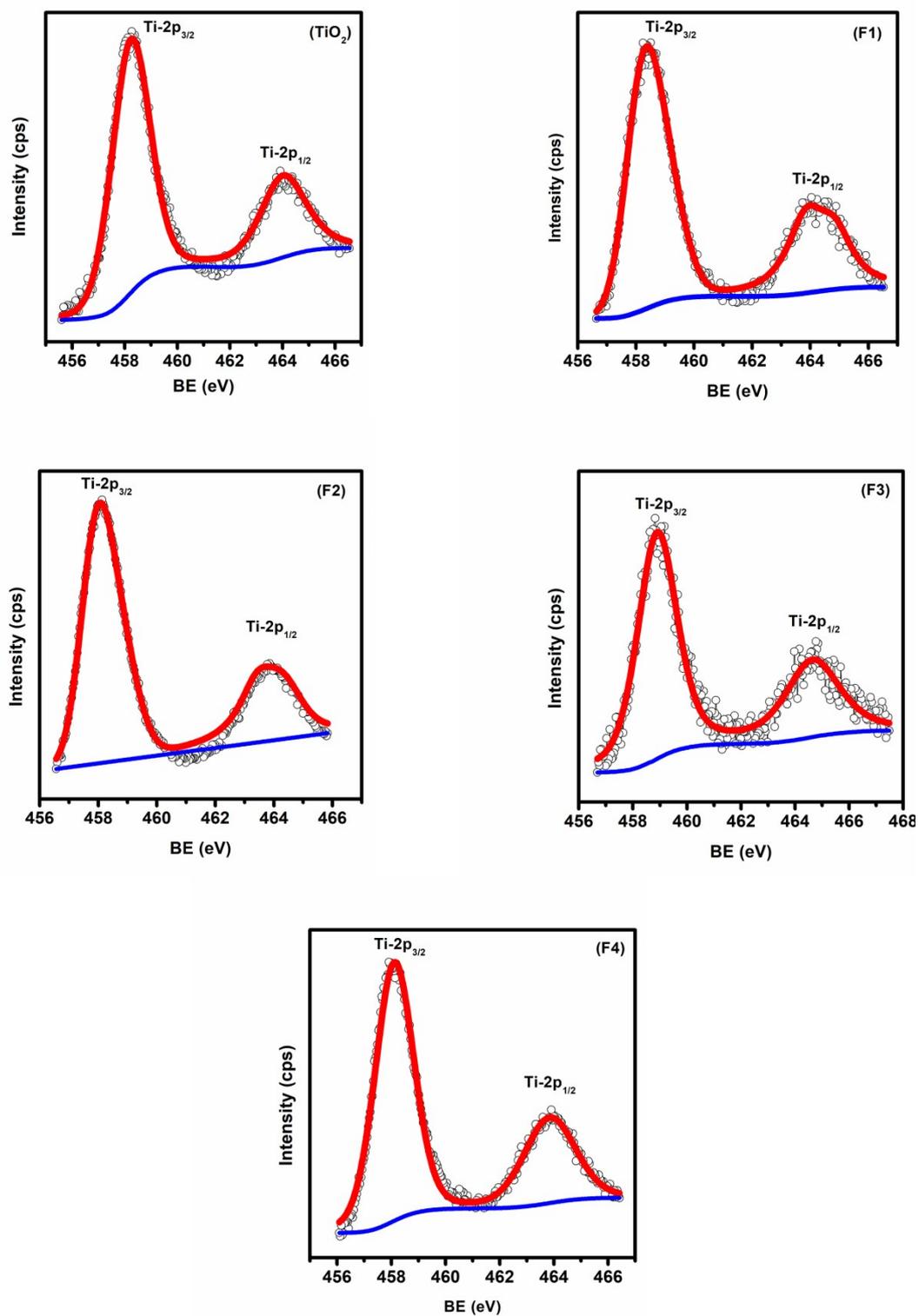


Fig. S2: Core-level XPS spectra of Ti-2p unimplanted TiO₂ and Au implanted TiO₂ matrix at different fluence (F1, F2, F3 and F4)

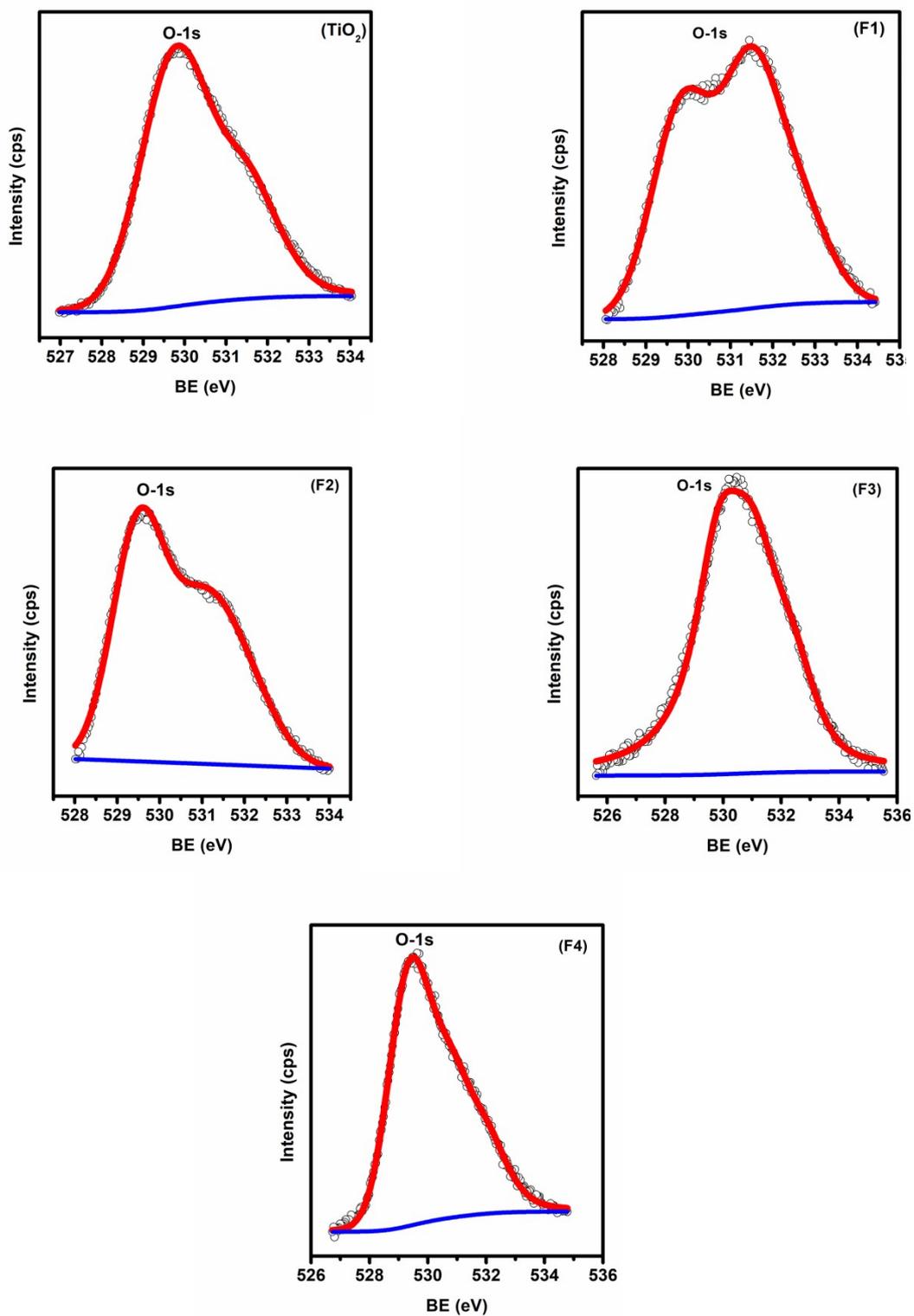


Fig. S3: Core-level XPS spectra of O-1s unimplanted TiO₂ and Au implanted TiO₂ matrix at different fluence (F1, F2, F3 and F4)

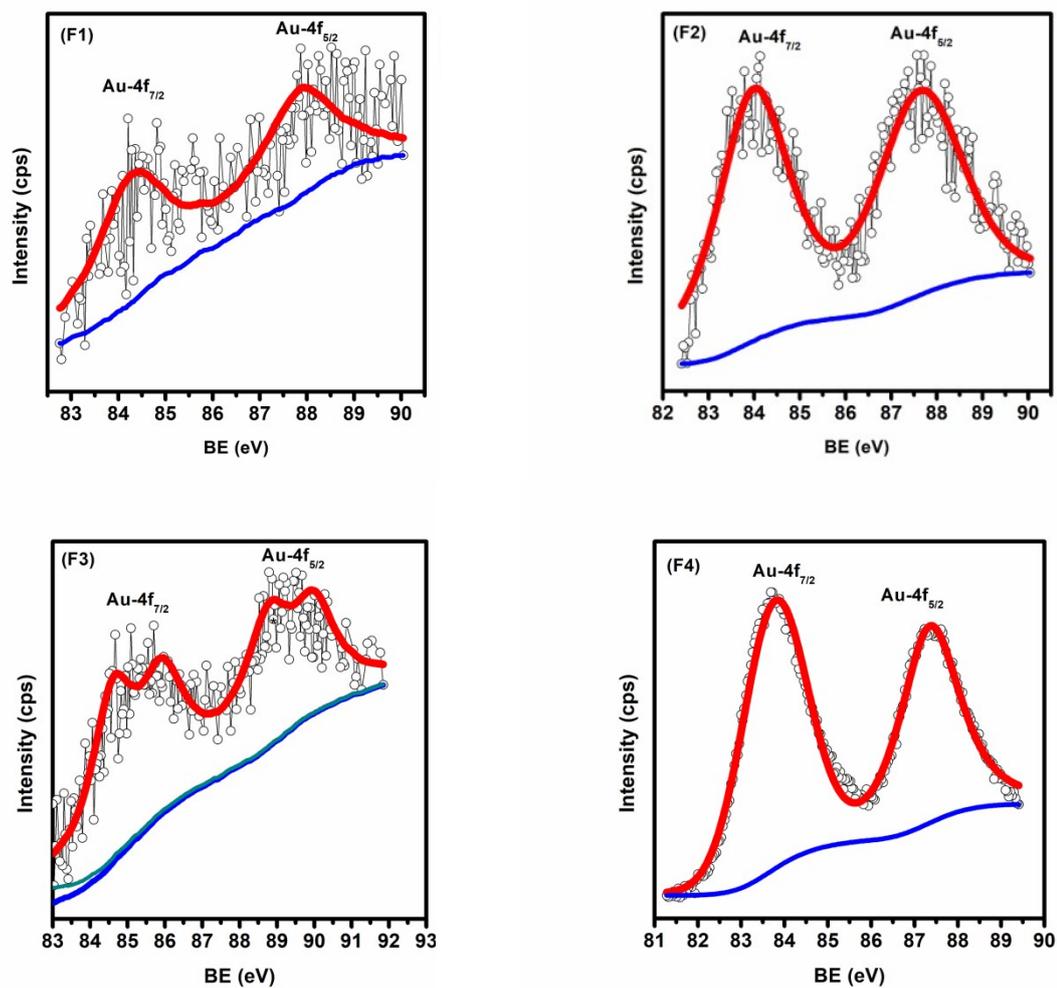


Fig. S4: Core-level XPS spectra of Au-4f of Au implanted TiO₂ matrix at different fluence (F1, F2, F3 and F4)